

## **DETAILED ACTION**

### ***Response to Arguments***

1. Applicant's arguments, filed 2/26/2008, with respect to the 35 USC 103(a) rejection has been fully considered and are persuasive. The examiner has withdrawn the rejection for the reasons set forth in the Remarks section dated 2/26/2008.

### **EXAMINER'S AMENDMENT**

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Daniel Hu on 4/23/2008.

The application has been amended as follows:

#### **IN THE CLAIMS**

In claim 29, line 4-5, after "amorphous film during the source supply process;" please insert "

supplying, during a second process, H<sub>2</sub> but not SiH<sub>4</sub> to the chamber;"

In claim 29, line 6, after "depositing the microcrystalline thin film on the substrate" please replace ", wherein prior to depositing the microcrystalline thin film, the supplying of  $\text{SiH}_4$  to the chamber is stopped" with " during the second process"

In claim 30, line 4, please delete "wherein depositing the microcrystalline thin film is performed during a source depositing process, and "

In claim 30, line 5-6, please replace "source depositing" with "second"

In claim 31, line 2, after "supplying" please insert ",during a first process,"

In claim 31, line 2, after "substrate is located;" please insert " supplying, during a second process,  $\text{H}_2$  but not  $\text{SiH}_4$  to the chamber;"

In claim 31, line 3, after "depositing the microcrystalline thin film on the substrate" please replace ", wherein prior to depositing the microcrystalline thin film, the supplying of  $\text{SiH}_4$  to the chamber is stopped" with " during the second process"

***Allowable Subject Matter***

3. Claims 1, 3-8, 10, 12-14, 17-18, and 26-31 are allowed.
4. The following is an examiner's statement of reasons for allowance:

5. The claims are allowed for the same reasons as set forth in the office action dated 8/15/2007 and substantially for the reasons set forth in the Remarks dated 2/26/2008. In summation, the examiner, after reviewing the prior art of record, find the applicants reasoning persuasive. The prior art applied in the office action dated 10/26/2007 discloses supplying  $\text{SiH}_4$  and  $\text{H}_2$  in a ratio so as to not deposit an amorphous thin film, however, none of the references alone or in combination teaches or makes obvious supplying, during a second process,  $\text{H}_2$  but not  $\text{SiH}_4$  to the chamber and depositing the microcrystalline thin film during this second supplying process. The combination of prior art applied 10/26/2007 is deficient in this regards for the reasons set forth by applicant in Remarks dated 2/26/2008.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### ***Conclusion***

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to DAVID TUROCY whose telephone number is (571)272-2940. The examiner can normally be reached on Monday-Friday 8:30-6:00, No 2nd Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy Meeks can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 1792

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